Amendment of the Claims under pct Article 34

27. (Added) The exposure apparatus according to claim 9, characterized in that the first illumination system comprises an optical member having a driving mechanism.

28. (Added) The exposure apparatus according to claim 27, characterized in that the second illumination system comprises an optical member not having a driving mechanism.

29. (Added) The exposure apparatus according to claim 27 or claim 28, characterized in that the purpose of the driving mechanism is provided to enable variation of the illumination shape or the illumination intensity of the exposure beam illuminating the mask.

30. (Added) The exposure apparatus according to any one of claims 27 to 29, characterized in that the optical member having the driving mechanism includes a movable blind enabling changes to the illumination range of the mask by the exposure beam.

31. (Added) The exposure apparatus according to claim 30, characterized in that a fixed blind to fix the illumination range of the mask by the exposure beam is provided in the first illumination system.

32. (Added) The exposure apparatus according to any one of claims 27 to 29, characterized in that the optical member having a driving mechanism includes an attenuator which attenuates the exposure beam.

33. (Added) The exposure apparatus according to any one of claims 9 to 11 or 27 to 32, characterized in that

the exposure main unit has a first support member to support the projection system which projects an image of an pattern of the mask onto the substrate, and

the second illumination system is fixed to the first support member, and the first illumination system is supported by a second support member independent of the first support member.

34. (Added) The exposure apparatus according to claim 33, characterized in that the exposure light source is positioned independently of the first support member and of the second support member.

35. (Added) The exposure apparatus according to claim 33 or claim 34, characterized in that the first support member and the second support member are each positioned on the same base, and the exposure light source is positioned independently of the base.

36. (Added) The exposure method according to claim 17, characterized in that the first illumination system comprises an optical member having a driving mechanism which is source of vibrations, and that the second illumination system comprises an optical member not having a driving mechanism which is a source of vibrations.

37. (Added) An exposure apparatus, having an exposure

light source which generates an exposure beam and a first support member which supports a projection system which projects an image of a pattern of a mask onto a substrate, and in which the exposure beam is used to transfer the pattern of the mask onto the substrate;

the exposure apparatus being characterized by having:

an illumination system which guides the exposure beam from the exposure light source to the mask and which has an optical member having a driving mechanism; and

a second support member which supports the optical member of the illumination system, independently of the first support member so as not to become a source of vibrations for the first support member.

38. (Added) The exposure apparatus according to claim 37, characterized in that

the illumination system has a first illumination system which includes the optical member having the driving mechanism and a second illumination system which does not include any optical members having driving mechanisms, and

the second illumination system is fixed to the first support member.

39. (Added) The exposure apparatus according to claim 37 or claim 38, characterized in that the driving mechanism is provided to enable variation of one of an illumination shape and an illumination intensity of the exposure beam illuminating the

mask.

40. (Added) The exposure apparatus according to any one of claims 37 to 39, characterized in that the first support member and the second support member are positioned on the same base.

41. (Added) The exposure apparatus according to any one of claims 37 to 40, characterized in that the exposure light source is positioned independently of the first support member and of the second support member.

42. (Added) An exposure apparatus which transfers the pattern of a mask onto a substrate, using an exposure beam generated by an exposure light source, characterized by comprising:

an illumination system which guides the exposure beam from the exposure light source to the mask; and

a first illumination unit, provided within the illumination system, holding a plurality of optical members driven by a driving unit, and in which an optical path of the exposure beam, including the plurality of optical members, is substantially sealed.

43. (Added) The exposure apparatus according to claim 42, characterized by also comprising a supply device which supplies gas, transmissive with respect to the exposure beam, to the sealed optical path.

44. (Added) The exposure apparatus according to claim 42 or claim 43, further comprising a second illumination system unit

which guides the exposure beam from the first illumination system unit to the mask, and a first support member which supports the projection system which projects the image of the pattern of the mask onto the substrate; and characterized in that:

the first illumination system unit is supported by a second support member independent from the first support member, and the second illumination system unit is fixed to the first support member.

45. (Added) The exposure apparatus according to claim 44, characterized in that the first support member and the second support member are positioned on the same base.

46. (Added) The exposure apparatus according to claim 44 or claim 45, characterized in that the exposure light source is positioned independently of the first support member and the second support member.

47. (Added) An exposure method in which an image of a pattern of a mask is transferred onto a substrate via a projection optical system supported by a first supporting member, using the exposure beam which is generated from an exposure light source, the exposure method being characterized by comprising the step of:

guiding the exposure beam from the exposure light source to the mask via an illumination system which has an optical element having a driving mechanism which is a source of vibrations;

supporting the optical element of the illumination system independently from the first support member; and

driving the driving mechanisms without transmitting the vibrations to the first support member.

48. (Added) The exposure method according to claim 47, characterized in that the driving mechanism is provided to drive the optical member to change the illumination conditions of the mask by the exposure beam.

49. (Added) The exposure method according to claim 47 or claim 48, characterized in that an optical path within the illumination system containing the optical member having the driving mechanism which is a source of vibration is substantially sealed, and a gas which is transmissive with respect to the exposure beam is supplied to the illumination system.

50. (Added) A device manufacturing method, characterized by comprising a process in which the pattern of a mask is transferred to a substrate, using the exposure apparatus of any one of claims 9 to 11 or 27 to 46.